## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):

HASEGAWA, et al.

Application No.:

**TBD** 

Filed:

October 1, 2003

For:

METHOD OF MANUFACTURING SEMICONDUCTOR

INTEGRATED CIRCUIT DEVICE, OPTICAL MASK THEREFOR,

ITS MANUFACTURING METHOD, AND MASK BLANKS

Expected

Group:

1756

Expected

Examiner:

Saleha R. Mohamedulla

## PRELIMINARY AMENDMENT

Mail Stop Patent Application Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 October 1, 2003

Sir:

Please amend the above-identified application, prior to examination thereof, as listed below and as set forth on the following pages:

Amendments to the Specification:

Remarks are included following the amendments: